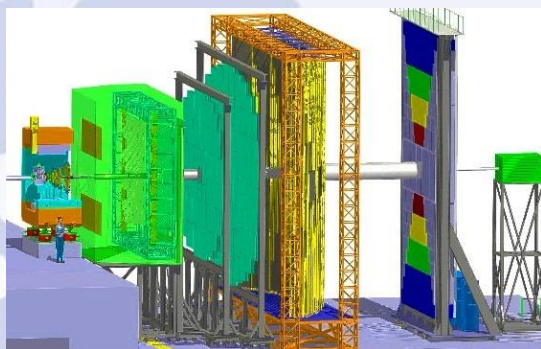




The Micro Channel Project



www.uni-frankfurt.de



M. Deveaux, 25th CBM Collaboration Meeting, Apr. 2015, GSI

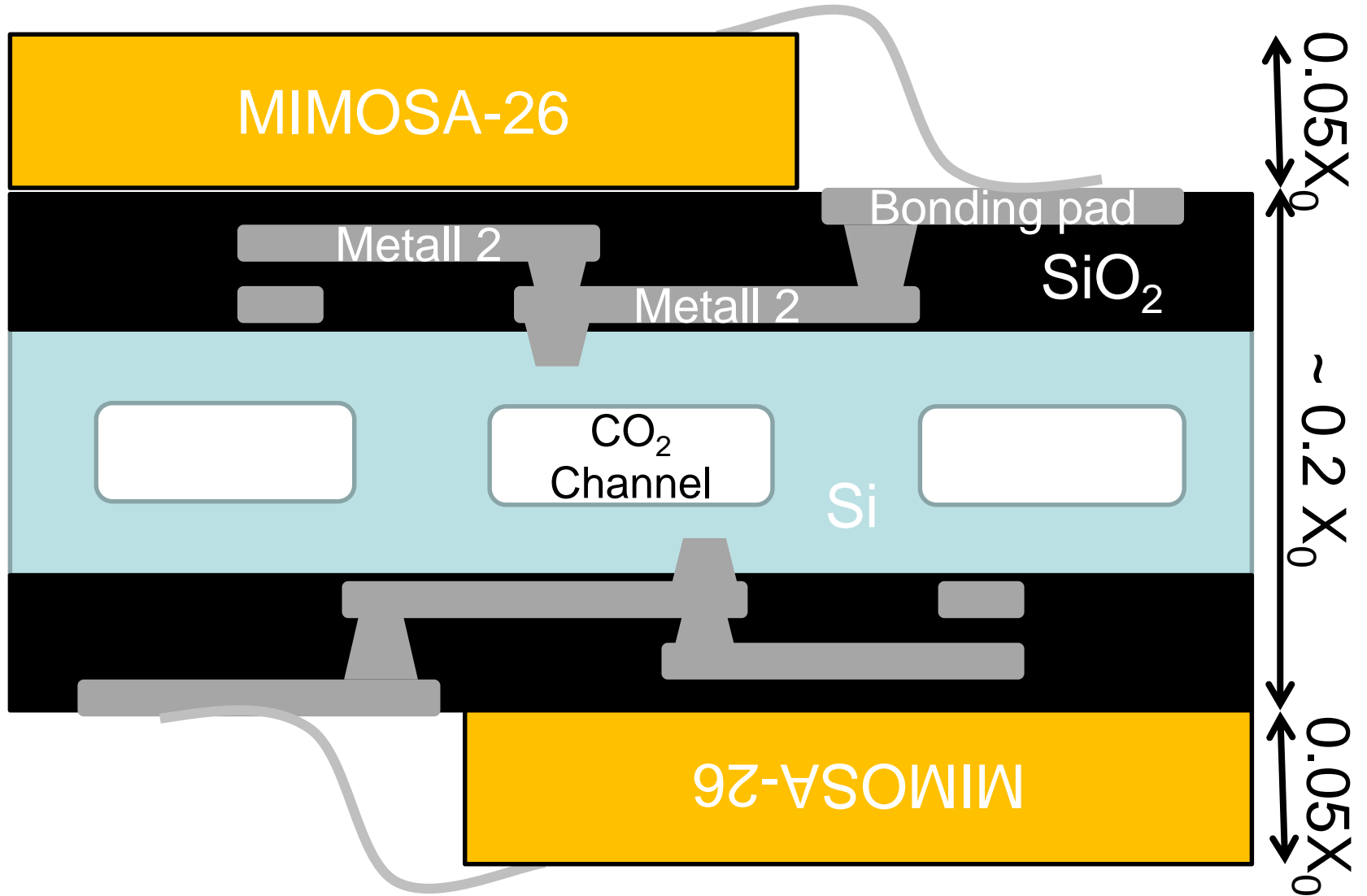
The situation

- MAPS provide a very light material budget
- The material budget of vertex detectors is dominated by:
 - Cables
 - Support
 - Cooling
- Support and cooling were integrated:
 - CVD-Diamond – IKF
 - Micro-Channel Cooling - CERN

The Idea

- Use lithographie to integrate cables and cooling into a vacuum compatible support.

How could it look like?



CiS Forschungsinstitut für Mikrosensorik und Photovoltaik GmbH

Konrad-Zuse-Straße 14

D-99099 Erfurt

Contact person: Dr. T. Frank (Manager Business unit MEMS)
(Lithography)

IKF Frankfurt/M (Integration)

The CBM-STC collaboration, J. Heuser (CO₂ – Cooling)

IPHC Strasbourg (Sensors, more?)

Project History

Vertex 2013 (Sept. 2013) – Started as a „beer idea“ aiming for a solution for the 2nd – 4th station of the generation CBM-MVD.
⇒ Financement idea: CBM – BMBF.

Late Sept. 2013 – Not part of the MVD- mainstream.
Try to find financement via EU – Horizon (Deadline 1st October).

Feb. 20th 2014 – Cost estimate from CiS (82kEUR)

March 2014 – Request 356kEUR from EU-Horizon including budget for IPHC.

June 2014 – Proposal rejected. Request to IPHC is willing to join the project despite not funding available => No interest.
⇒ Project abandoned

2015 – CiS proposes to provide deliverables for free. IPHC willing to join in. Restart aiming for DFG-Funding.

Design rules

Metall lines: 2 per side, vias and substrate contacts possible

Material of the traces: AlSi (equivalent to Al).

Thickness of the traces: 1,8 μm (standard), 3 μm feasible.

Minimum width of the traces: 20 μm

Minimum distance of the traces: 20 μm

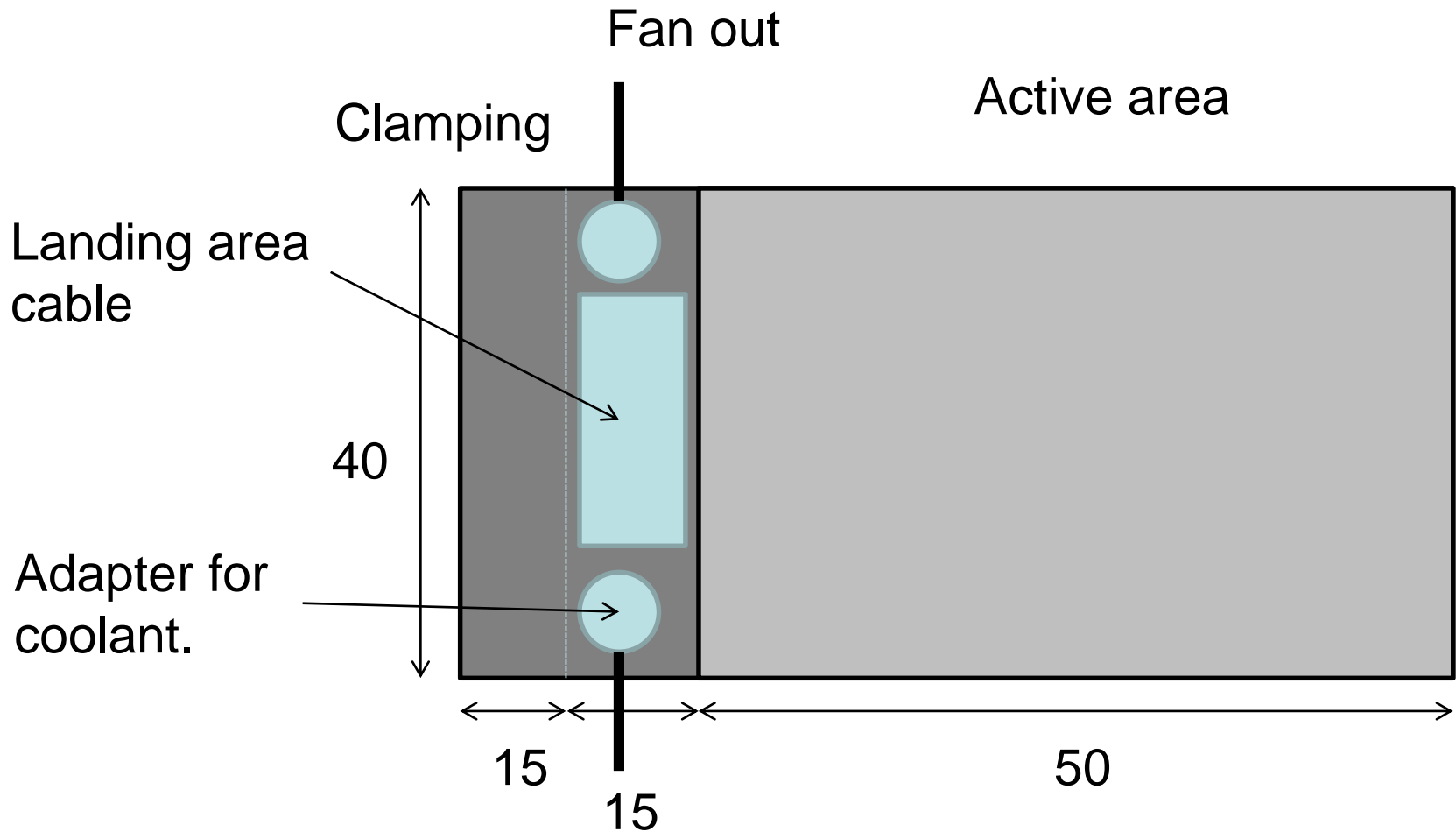
Passivation: Between traces and at surface.

Bonding pads: AlSi

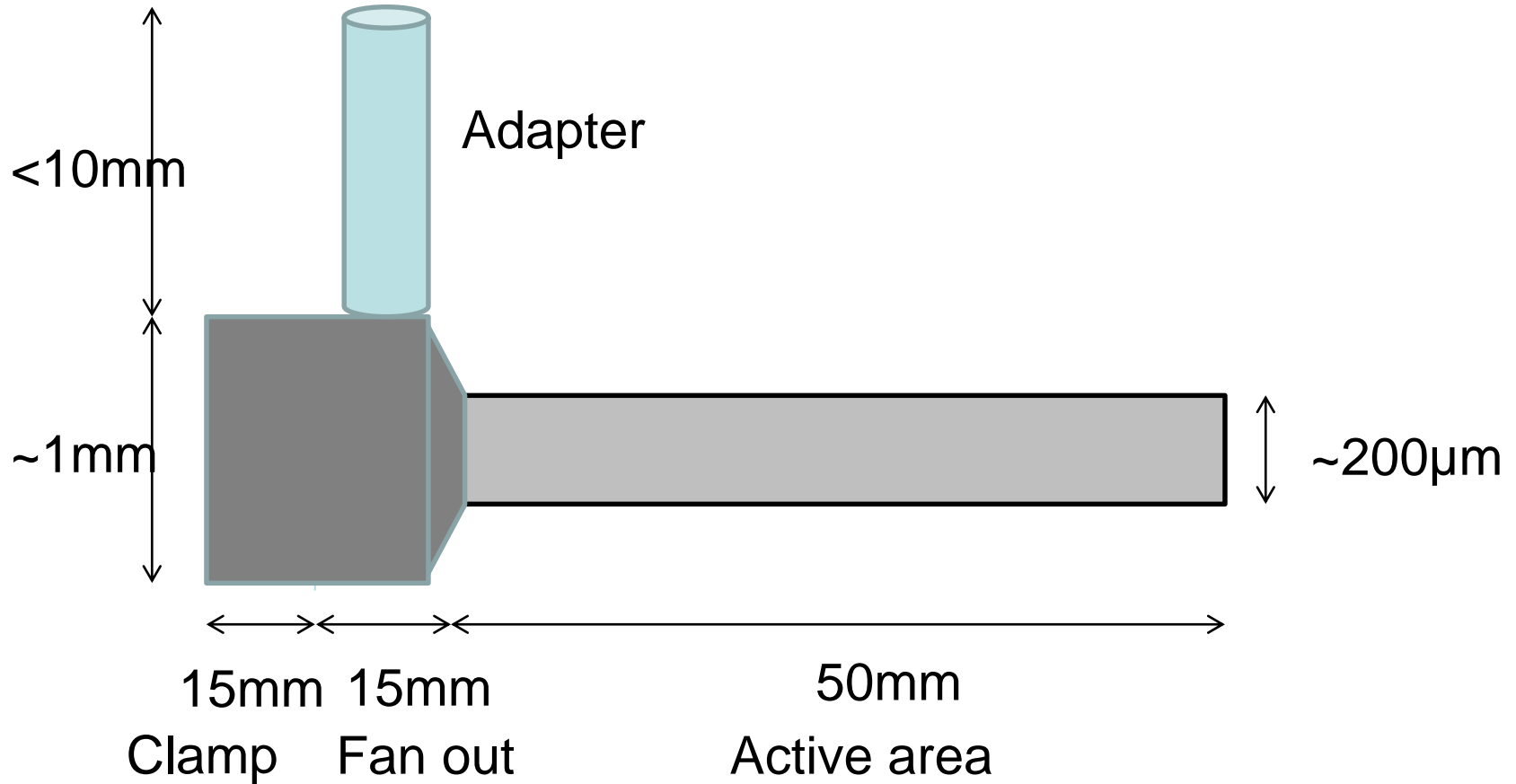
Thinning of silicon:

- A local thinning of the wafer is possible by etching. The borders are diagonal (54.7°).
- Borders may be crossed by metal lines

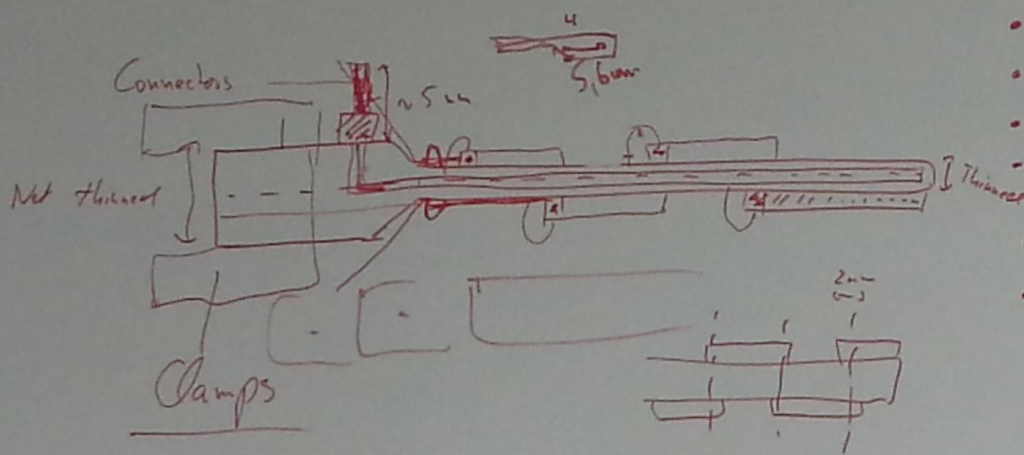
Design of the object (draft, top view)



Design of the object (draft, side view)

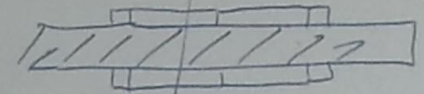


Sensor arrangement (draft)



- 2 µm Al
- Vias possible
- Metall ↔ Si Vias possible
- 2 Metal per side

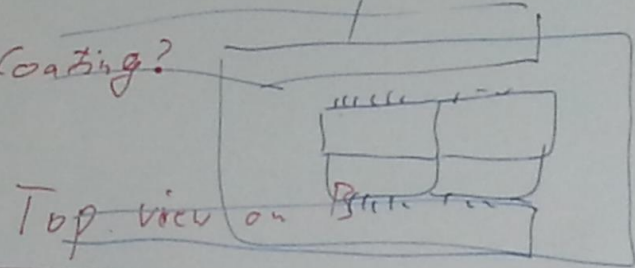
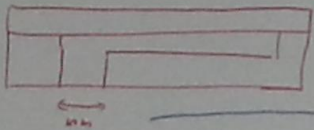
→ Electric Dummy
→ Cabling Dummy → Final



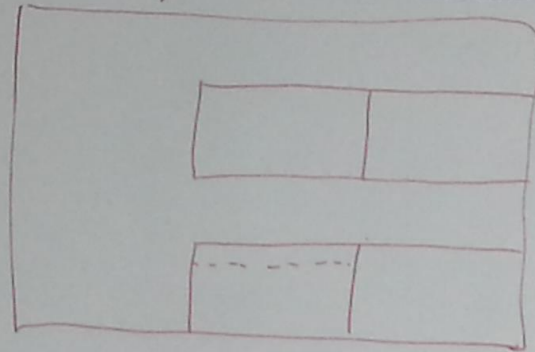
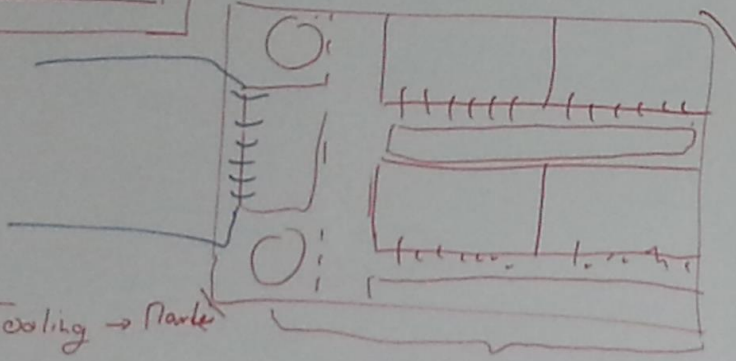
- Insulating Glue?
~~Traces~~ Passivation

- ~~Good~~ Nickel Gold Coating?

- Local thinning possible?
4"

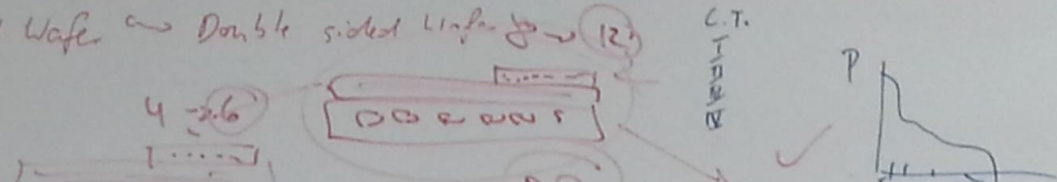


Top view on ~~Back~~ Front



- Tooling → Mark

- Dummy : Single sided Wafer → Double sided Wafer → 12"
- Alignment Goal : 100 µm
- 1/2" of Whisker



Mechanical Demonstrator
(Cooling channels only)



Electrical Demonstrator
(Traces only)



Fully integrated device

8 Sensors

8 Sensors

Global strategy

TASKS/Subtasks	2015				2016				2017			
	Q1	Q2	Q3	Q4	Q1	Q2	Q3	Q4	Q1	Q2	Q3	Q4
TASK 2: Development of an actively cooled support with integrated electrical circuits												
2.1 Technology development of a micro-integrated support	■	■	■	■	■							
2.1.1 Design and construction support with cooling channels	4	■	6a									
2.1.2 Design and construction support with aluminum traces	5	■	6b									
2.1.3 Integration of sensors				7								
2.1.4 Intermediate test				■	8							
2.2 Development of actively cooled, fully integrated support						■	■	■	■	■	■	■
2.2.1 Design based on results of task 2.1						9						
2.2.2 Construction of supports							■	10				
2.2.3 Integration of sensors									11			
2.2.4 Test of the system									■	■	12	■

Delayed by ~6 month

↑
Submission DFG proposal

↑
Decision DFG proposal